

36970-U 8-Sept-02
16/073874
02/14/02

PATENT NUMBER and
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM	FILING DATE	CLASS	SUBCLASS	GAU	EXAMINER
10073874	02/14/2002	430	5	1756	RO-ASCO

**APPLICANTS: Shoki Tsutomu; Hosoya Morio;

**CONTINUING DATA VERIFIED:

AL NONE

** FOREIGN APPLICATIONS VERIFIED:

JAPAN 37034/2001 02/14/2001 *AL*

PG-PUB DO NOT PUBLISH ☐

RESCIND ☐

Foreign priority claimed ☒ yes ☐ no

35 USC 119 conditions met ☒ yes ☐ no

Verified and Acknowledged Examiners's initials *AL*

ATTORNEY DOCKET NO

Q68554

TITLE : Reflection type mask blank for EUV exposure and reflection type mask for EUV exposure as well as method of producing the mask

U.S. DEPT. OF COMM./PAT. & TM.-PTO-436L (Rev. 12-94)

NOTICE OF ALLOWANCE MAILED		CLAIMS ALLOWED	
		Total Claims	Print Claim for 0.0
Assistant Examiner		DRAWING	
		Sheets Drwg.	Figs. Drwg.
Amount Due		Print Fig.	
Date Paid			
Primary Examiner		Application Examiner	
<input type="checkbox"/> TERMINAL DISCLAIMER		PREPARED FOR ISSUE	
WARNING: The information disclosed herein may be restricted. Unauthorized disclosure may be prohibited by the United States Code Title 35, Sections 122, 181 and 368; Possession outside the U.S. Patent & Trademark Office is restricted to authorized employees and contractors only.			

FILED WITH:

☒ DISK (CRF)

☒ CD-ROM

(Attached in pocket on right inside flap)